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## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re PATENT APPLICATION of:

Confirmation Number: 4455

JOOST JEROEN OTTENS, ET AL.

Group Art Unit: 1756

Filed: December 23, 2003

Application No.: 10/743,272

Examiner: Christopher G. Young

Title: OPTIMIZED CORRECTION OF WAFER THERMAL DEFORMATIONS IN A

LITHOGRAPHIC PROCESS

## RESPONSE TO RESTRICTION REQUIREMENT

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

In response to the Office Action dated October 12, 2006, Applicant elects, without traverse, for examination: Group I, encompassing claims 1-34, drawn to methods of correcting thermally induced field deformations.

Applicant reserves the right to file a divisional application for non-elected claims at a future date, if necessary.

Respectfully submitted,

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Date: November 3, 2006

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